



## G. Device &amp; Process Modeling, Simulation and Reliability 분과

2019년 2월 15일(금), 11:00-12:30

Room B (마루홀, 2층)

## [FB2-G] Advanced Devices III : Technology &amp; Simulation

좌장: 박정수 수석(SK하이닉스), 이정수 교수(POSTECH)

<b>FB2-G-1</b> <b>11:00-11:15</b>	<b>RDF/LER-Induced Performance Variation-Immune Effect of Metal-Interlayer-Semiconductor Source/Drain on n-Ge Junctionless Field-Effect Transistor</b> Seung-Geun Jung, Mu-Yeoung Son, Hyeok Jeon, Tae-Hyun Kim, Young-Hun Shin, and Hyun-Yong Yu <i>Department of Electronic Engineering, Korea University</i>
<b>FB2-G-2</b> <b>11:15-11:30</b>	<b>A Development of High Reliability HV ESD Power Clamp for Large Display Driver Ics</b> Wonsuk Park, Jungwoo Han, Jowoon Lee, Youngchul Kim, and Joontae Jang <i>Department of Electronic Engineering, DB HiTek</i>
<b>FB2-G-3</b> <b>11:30-11:45</b>	<b>Domain Wall Dynamics for Transient NC Effect in Ferroelectric BaTiO<sub>3</sub> Thin Films</b> Hyeon Woo Park <sup>1,2</sup> , Yong Bin Lee <sup>1,2</sup> , Jangho Roh <sup>1,2</sup> , Keum Do Kim <sup>1,2</sup> , Young Hwan Lee <sup>1,2</sup> , Seung Dam Hyun <sup>1,2</sup> , Baeksu Kim <sup>1,2</sup> , Ho Hyeon Kim <sup>1,2</sup> , Beom Yong Kim <sup>1,2</sup> , Taehwan Moon <sup>1,2</sup> , and Cheol Seong Hwang <sup>1,2</sup> <sup>1</sup> <i>Department of Material Science and Engineering, Seoul National University,</i> <sup>2</sup> <i>Inter-University Semiconductor Research Center, Seoul National University</i>
<b>FB2-G-4</b> <b>11:45-12:00</b>	<b>Effect of Boron and Gallium Doping on the Lattice Parameters in Si and Si<sub>1-x</sub>Ge<sub>x</sub></b> Minhyeong Lee and Dae-Hong Ko <i>Department of Materials Science and Engineering, Yonsei University</i>
<b>FB2-G-5</b> <b>12:00-12:15</b>	<b>Analytical Model of Static I-V and Flicker Noise for Tunnel Field-Effect Transistors</b> Young-Hun Park <sup>1</sup> , Hyeong-Sub Song <sup>2</sup> , Dong-Hwan Lim <sup>3</sup> , Chang-Hwan Choi <sup>3</sup> , Hi-Deok Lee <sup>2</sup> , and Ji-Woon Yang <sup>1</sup> <sup>1</sup> <i>Department of Electronic &amp; Information Engineering, Korea University,</i> <sup>2</sup> <i>Department of Electronic Engineering, Chungnam National University,</i> <sup>3</sup> <i>Division of Mater. Sci. and Engineering, Hanyang University</i>
<b>FB2-G-6</b> <b>12:15-12:30</b>	<b>Performance Improvement of Low Frequency Noise Characteristics in Gate-Last FDSOI Tunneling Field Effect Transistor with Deuterium Passivation</b> Hyeong-Sub Song <sup>1</sup> , So-Yeong Kim <sup>1</sup> , Sung-Kyu Kwon <sup>1</sup> , Hyun-Dong Song <sup>1</sup> , Gawon Lee <sup>1</sup> , Dong-Hwan Lim <sup>2</sup> , Chang-Hwan Choi <sup>2</sup> , and Hi-Deok Lee <sup>1</sup> <sup>1</sup> <i>Department of Electronics Engineering, Chungnam National University,</i> <sup>2</sup> <i>Division of Materials Science and Engineering, Hanyang University</i>